



Defects in silicon crystals

- Some very basic remarks -

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*People are like crystals. It is the defects in them
that make them interesting.* Sir F.Charles Frank

Perfection has one grave defect : it is apt to be dull

William Somerset Maugham

- Defects give silicon crystals new properties
- These properties can be useful (e.g. doping, defect engineering) or not (e.g. radiation damage, metal contaminations)



Outline

- Silicon and Silicon crystal structure
- Defect types in silicon crystals
- Silicon doping (Dopants = Defects)
- Radiation induced defects
- What are defects doing to detectors?
- How to measure defects?
- Coffee

Easy
level

More
difficult
level

Relax level

Silicon



Atomic number = 14 Atomic mass 28.0855 amu

- Most abundant solid element on earth 50% O, 26% Si, 8% Al, 5% Fe, 3% Ca, ...
- 90% of earth's crust is composed of silica (SiO_2) and silicate !



Very pure sand or quartz

(e.g. from Australia or Nova Scotia in Canada)

$\approx 99\%$ SiO_2

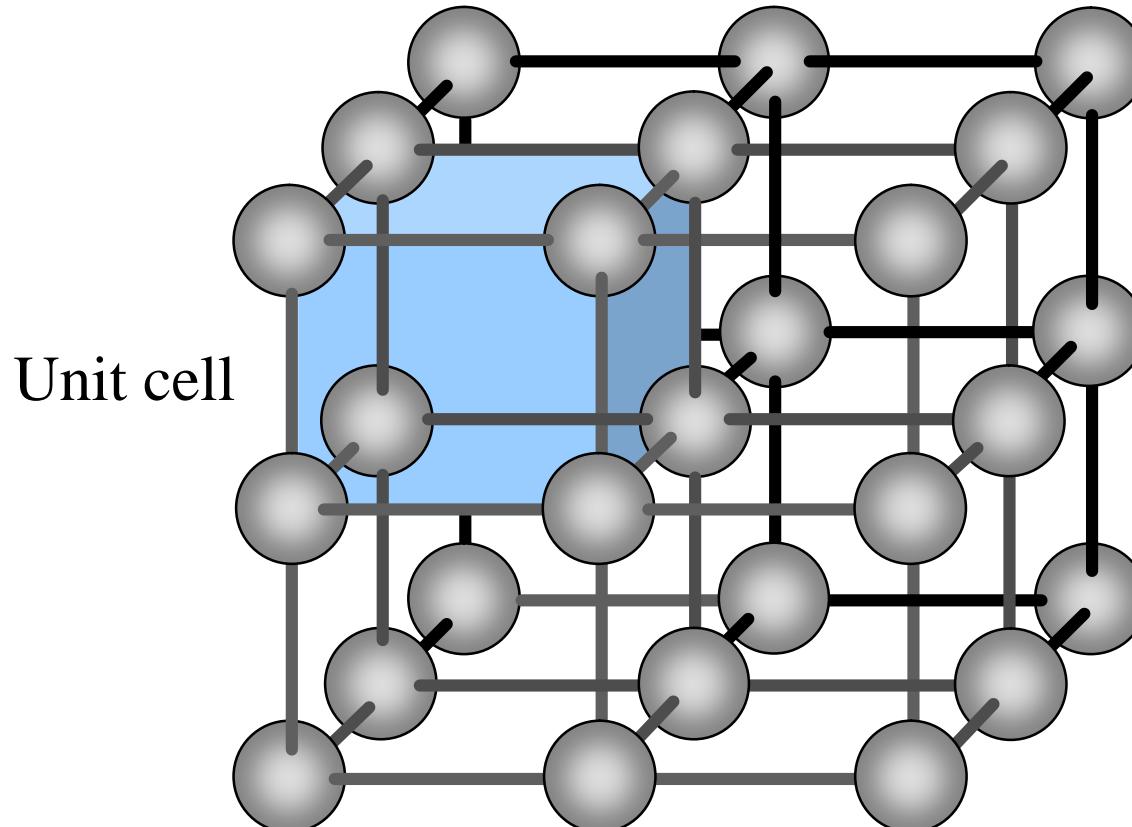
$\approx 1\%$ Al_2O_3 , Fe_2O_3 , TiO_2 (CaO, MgO)

?

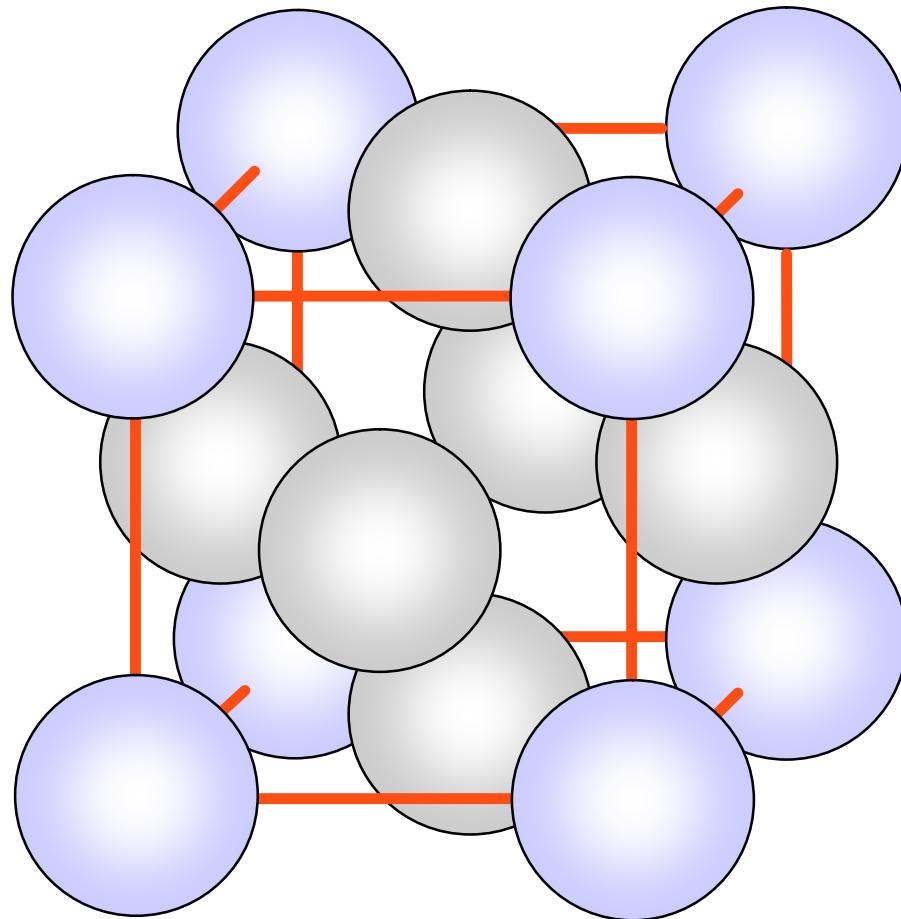
Silicon

Another coffee
meeting ?

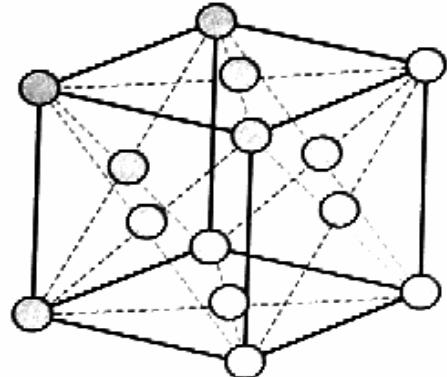
Unit Cell in 3-D Structure



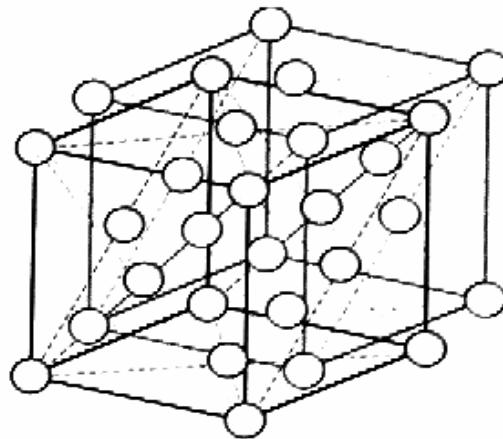
Faced-centered Cubic (FCC) Unit Cell



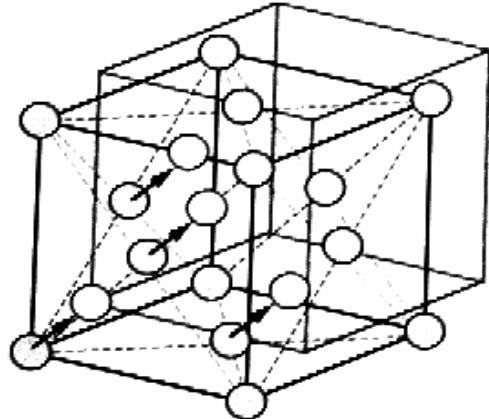
Silicon Crystal Structure



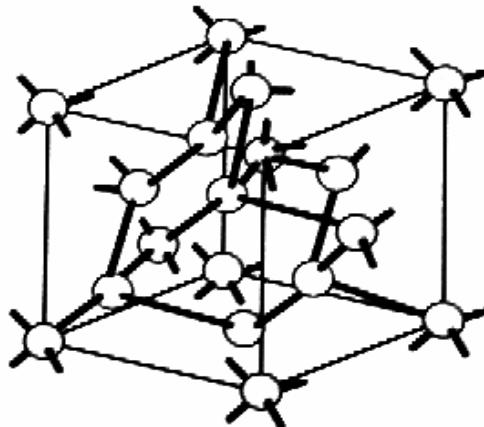
Basic FCC Cell



Merged FCC Cells



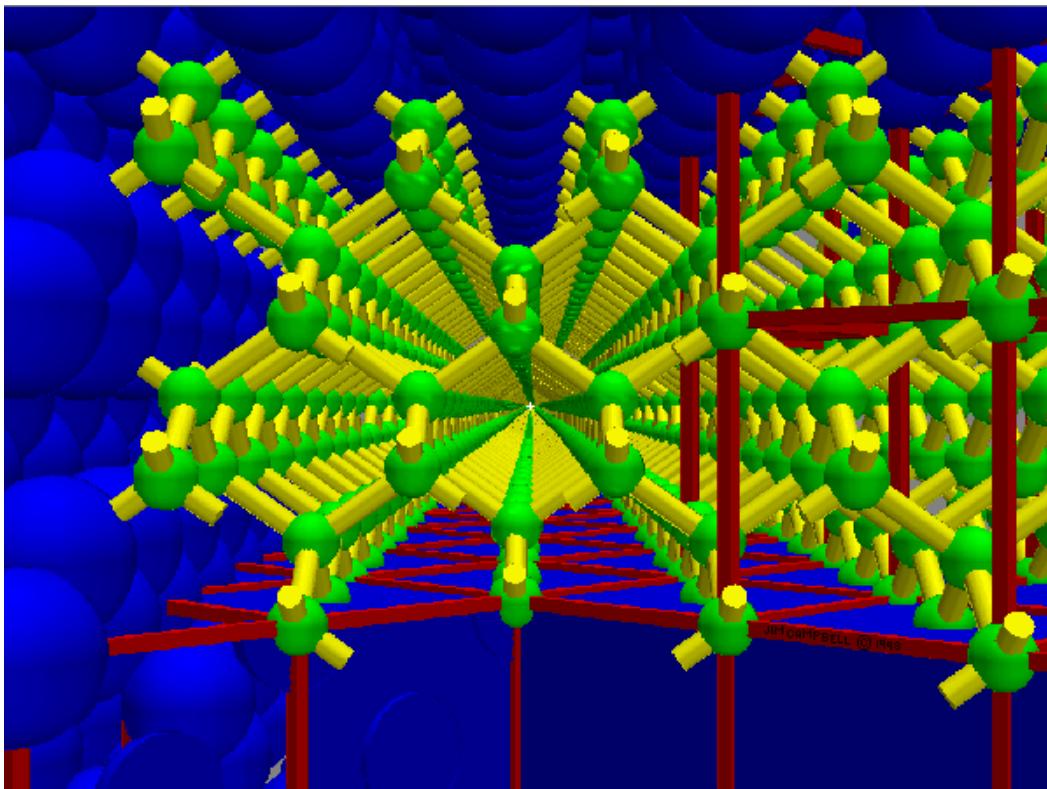
Omitting atoms
outside Cell



Bonding of Atoms

**Silicon has the basic diamond crystal structure:
two merged FCC cells offset by $a/4$ in x, y and z**

Silicon Crystal Structure

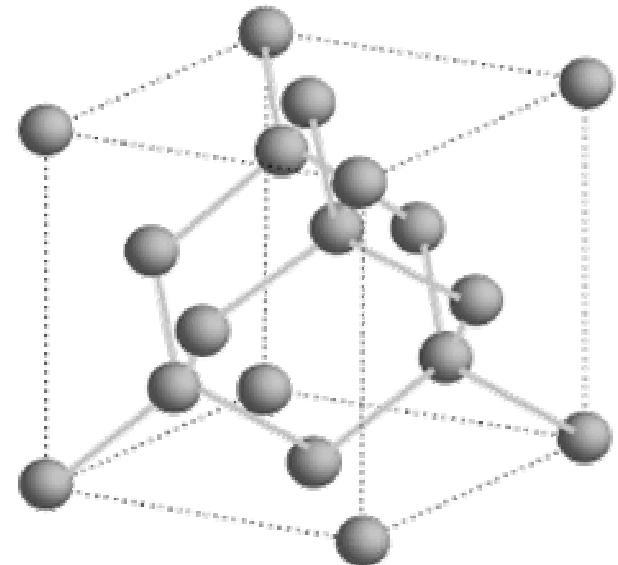


Silicon crystallizes in the same pattern as **Diamond**, in a structure called "two interpenetrating face-centered cubic" primitive lattices. The lines between silicon atoms in the lattice illustration indicate nearest-neighbor bonds. The cube side for silicon is 0.543 nm.

[Link: BC8 Structure of Silicon](#)

[Link: Silicon lattice \(wrl\)](#)

[Link: Silicon lattice with bonds \(wrl\)](#)

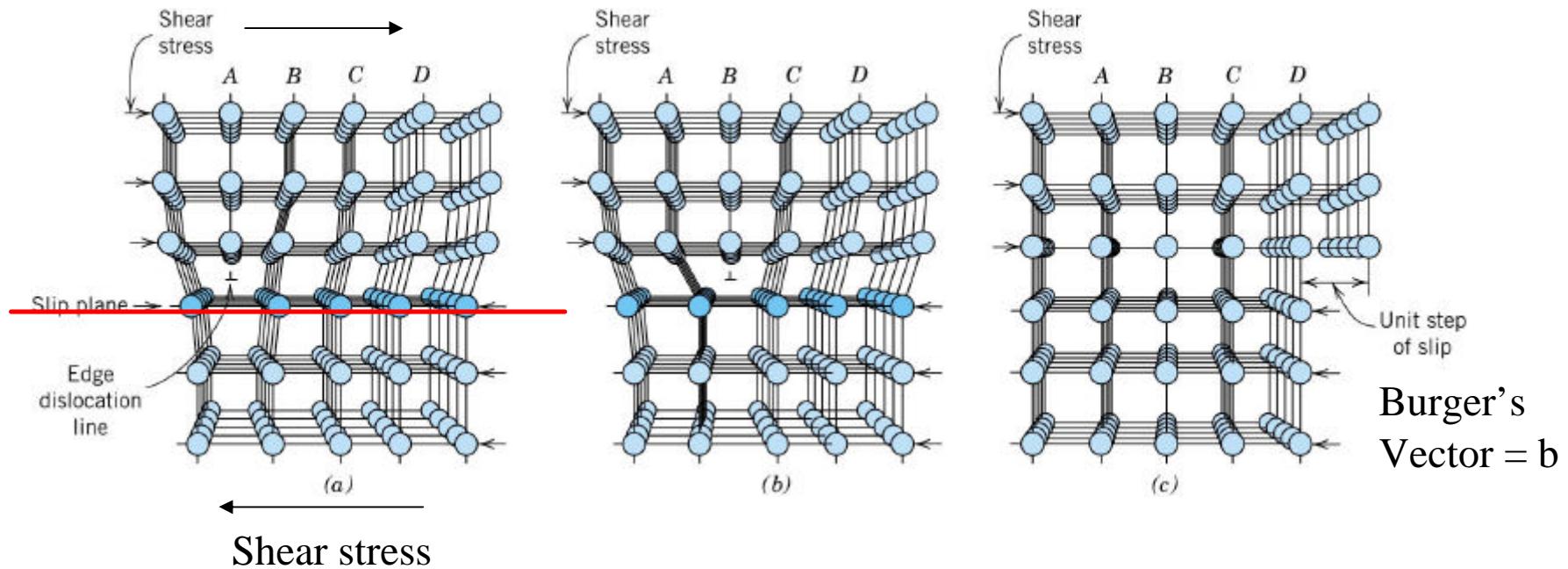


Outline

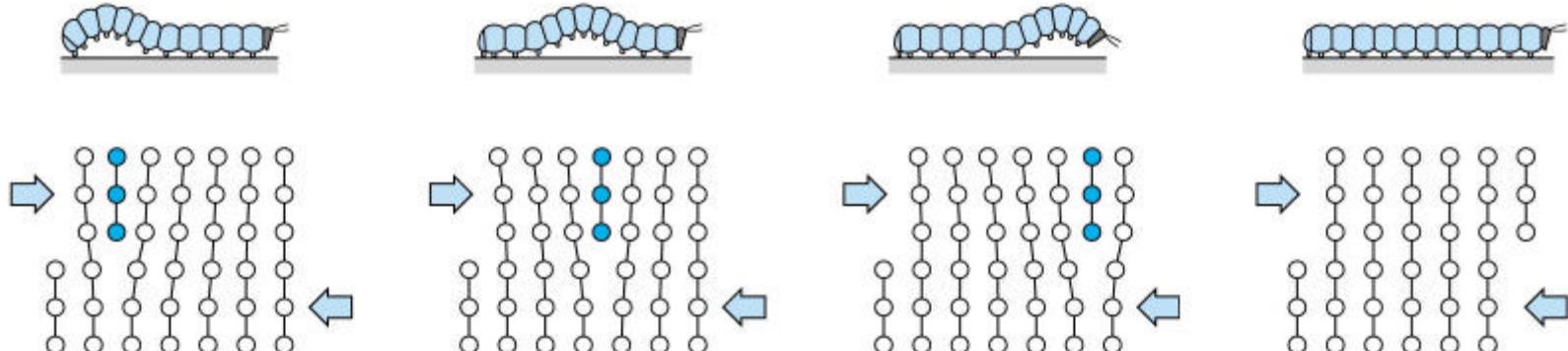
- Silicon and Silicon crystal structure
- Defect types in silicon crystals
 - Lattice defects (Dislocations)
 - Point defects (e.g. Impurities)
 - Cluster defects and Precipitates
- Silicon doping (Dopants = Defects)
- Radiation induced defects
- What are defects doing to detectors?
- How to measure defects?
- Coffee



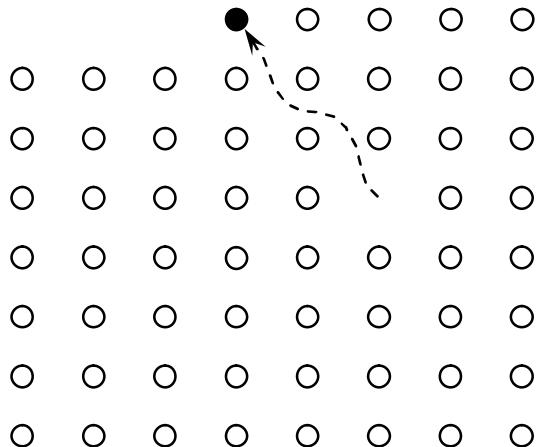
Dislocations



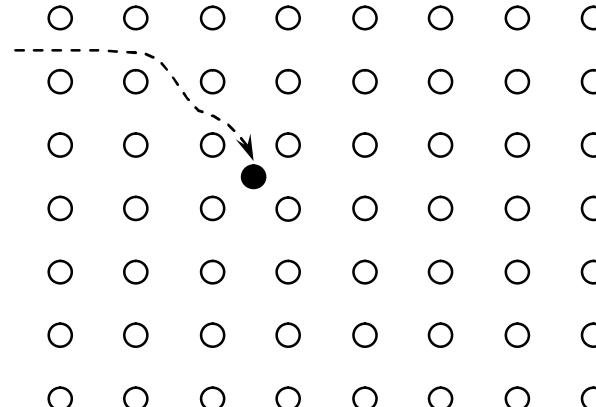
The caterpillar or rug-moving analogy



Point Defects

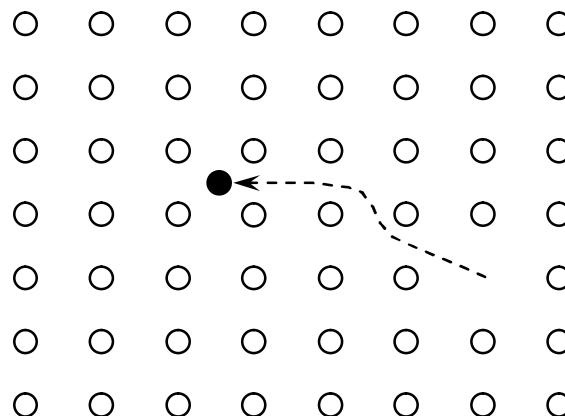


Vacancy defect



Interstitial defect

[Link: Split-interstitial \(wrl\)](#)

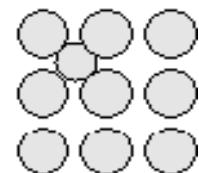
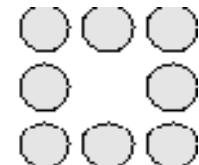


Frenkel defect



- **Intrinsic defects:**

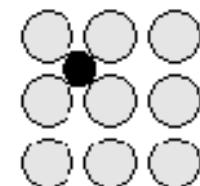
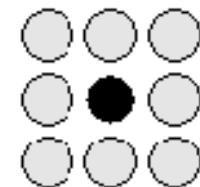
- The **Vacancy (denoted V)**: an atom is removed.
- The **Self-interstitial (denoted I)**: a host atom sits in a normally unoccupied site or interstice (various sites: bond centres, tetrahedral sites, interstitial + displaced regular atom).



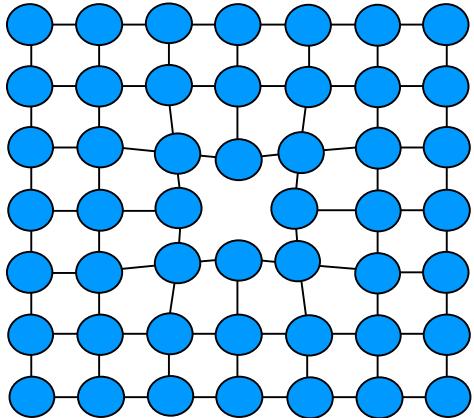
- **Extrinsic defects: due to an impurity.**

These can be:

- **Substitutional**, such as carbon substitutional (denoted C_s)
- **Interstitial** (such as the carbon interstitial (denoted C_i)).

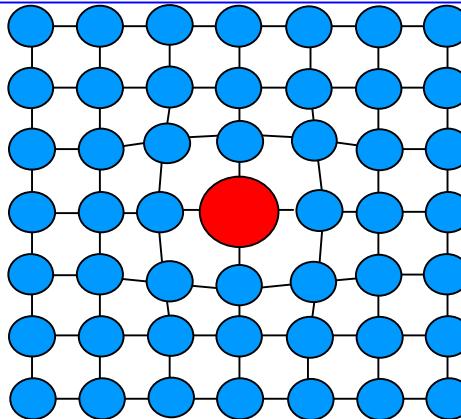


Point Defects - Lattice strain



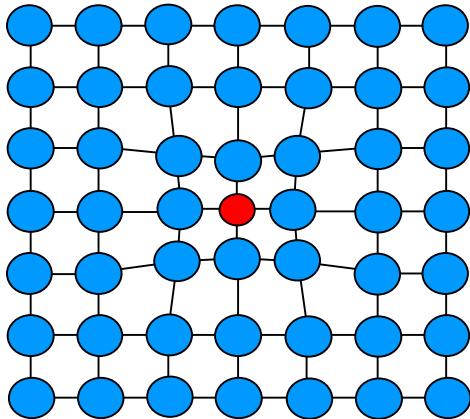
(a) A vacancy in the crystal.

[Link: Vacancy - Hydrogen Defect](#)



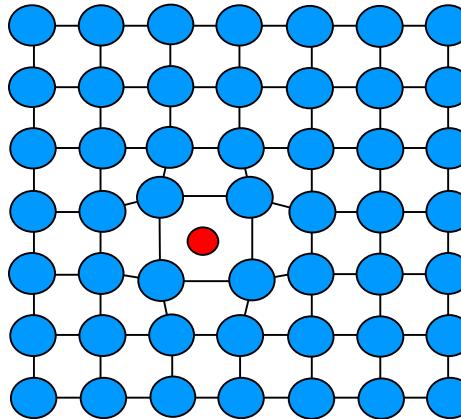
Ge, Sn

(b) A substitutional impurity in the crystal. The impurity atom is larger than the host atom.



C_s

(c) A substitutional impurity in the crystal. The impurity atom is smaller than the host atom.



C_i, O_i

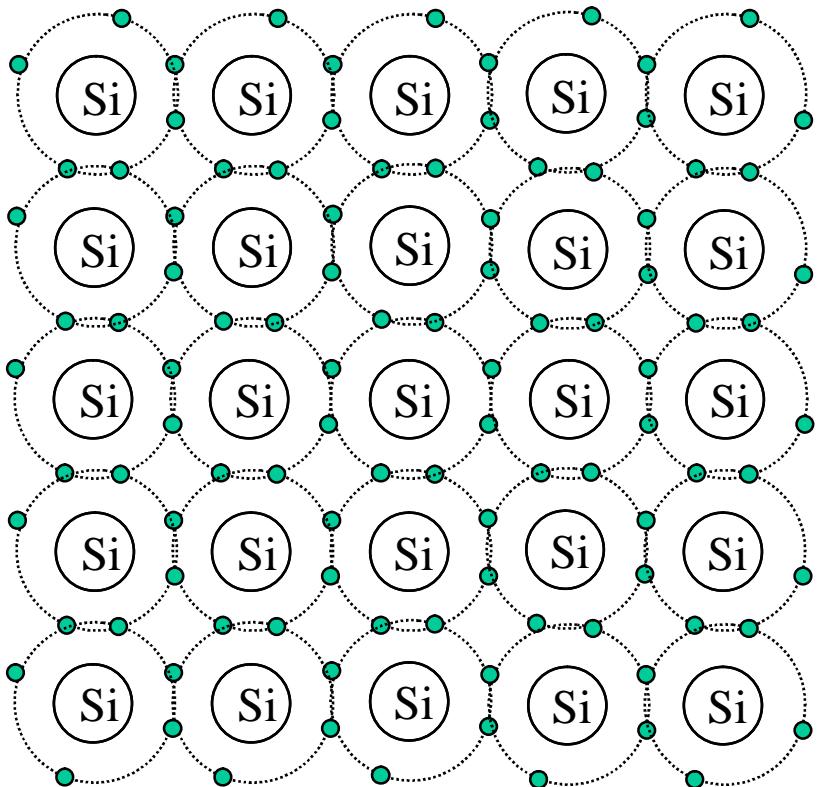
(d) An interstitial impurity in the crystal. It occupies an empty space between host atoms.

Outline

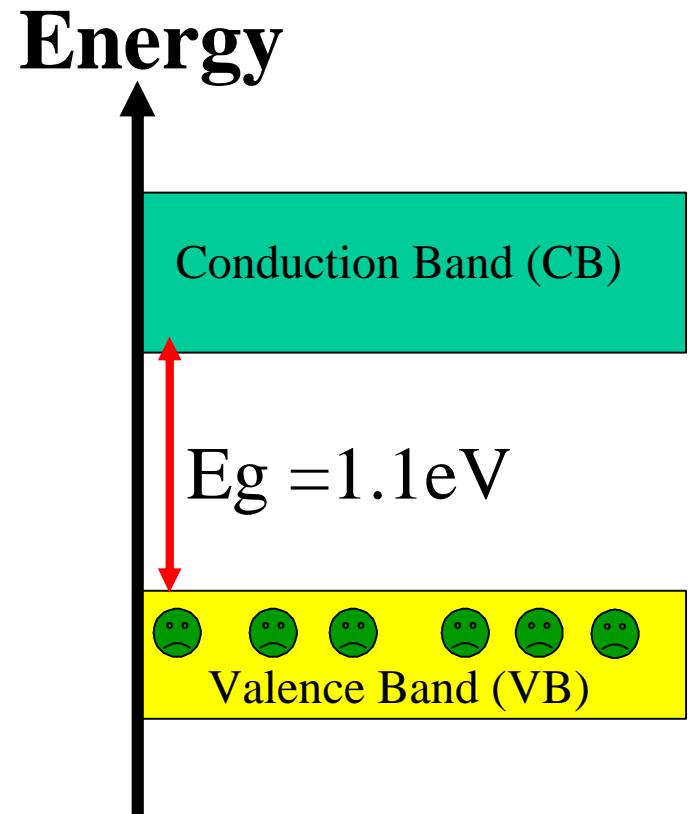
- Silicon and Silicon crystal structure
- Defect types in silicon crystals
- Silicon doping (Dopants = Defects)
 - Intrinsic silicon
 - n-type silicon
 - p-type silicon
- Radiation induced defects
- What are defects doing to detectors?
- How to measure defects?
- Coffee



Covalent Bonding of Pure Silicon

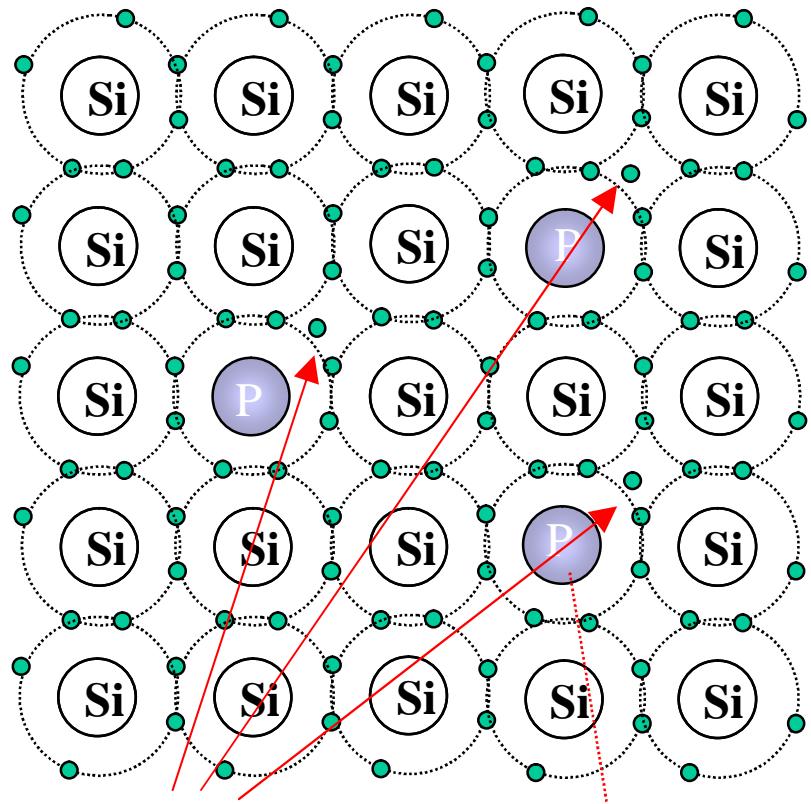


Silicon atoms share valence electrons to form insulator-like bonds.



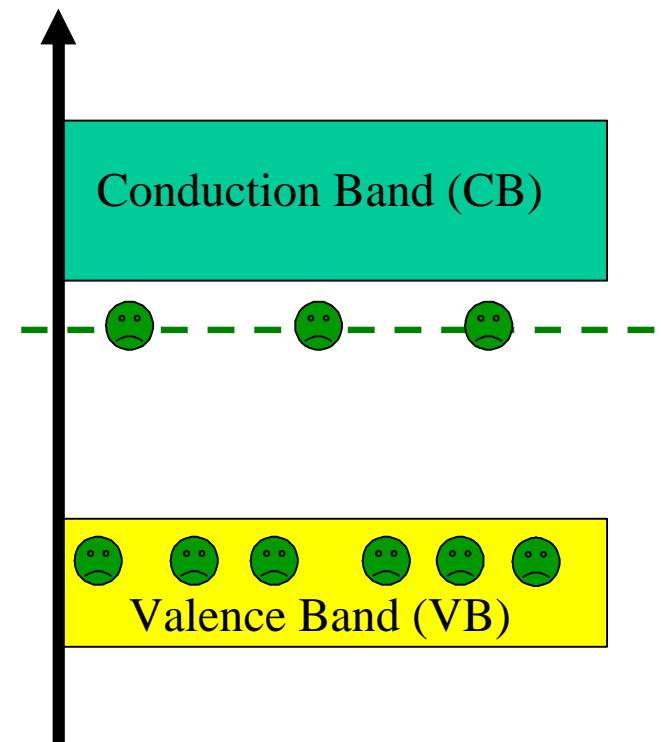


**Donor atoms provide excess electrons
to form n-type silicon.**



Excess electron (-)

Phosphorus atom
serves as n-type
dopant



Conduction in n-Type Silicon

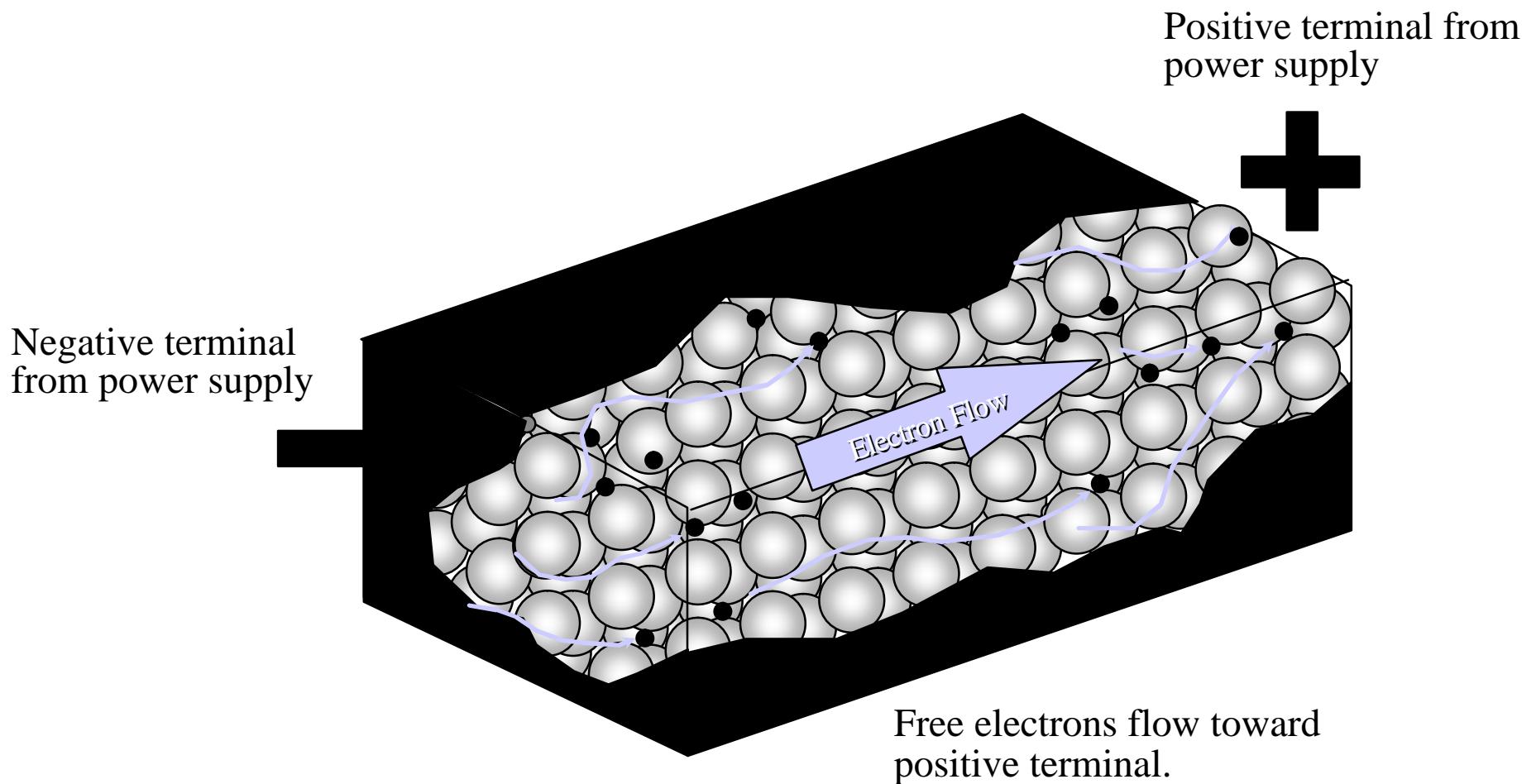
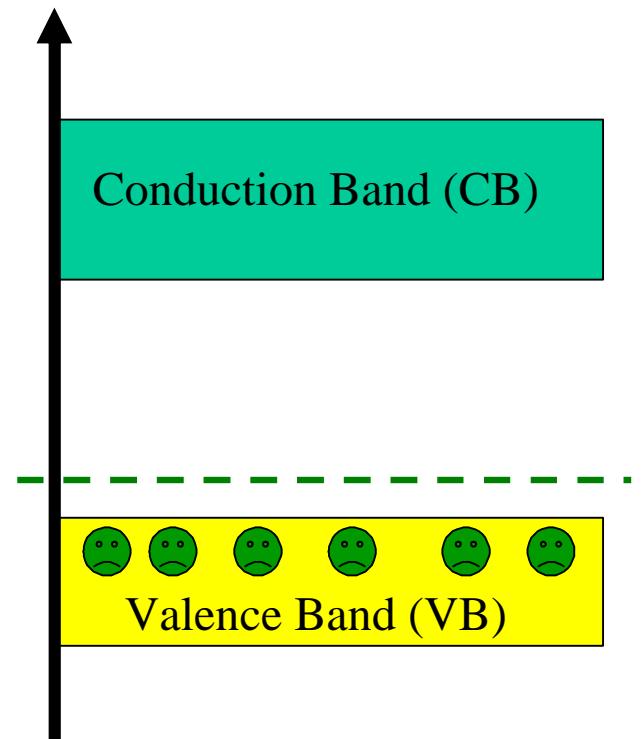
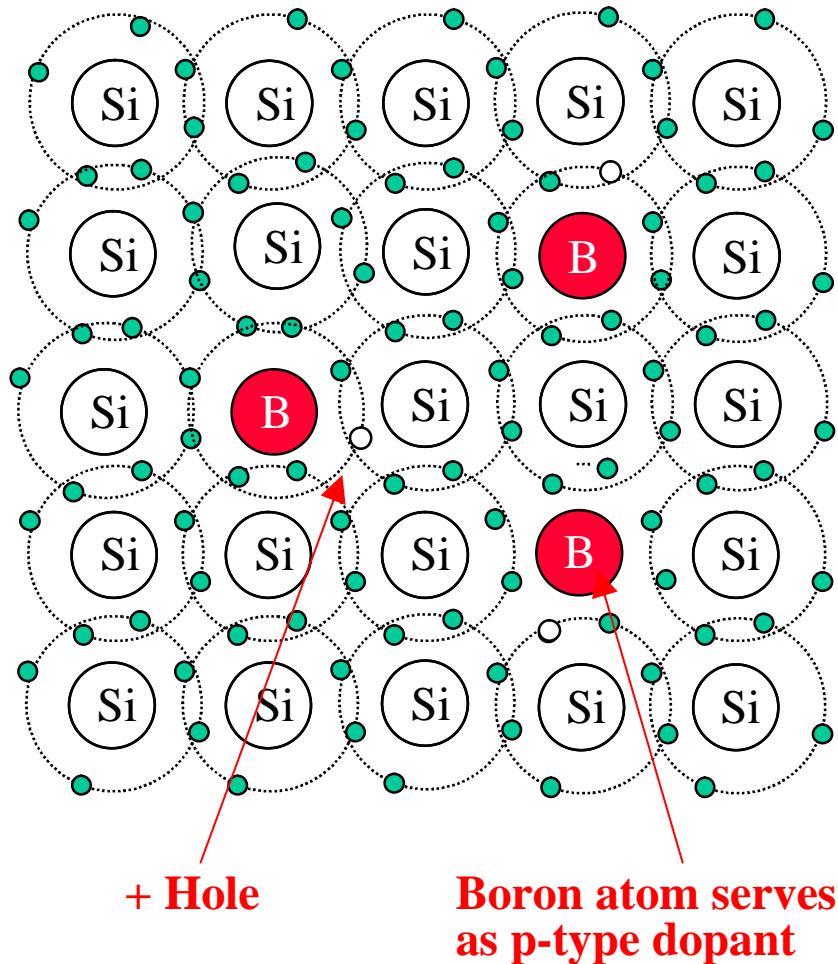


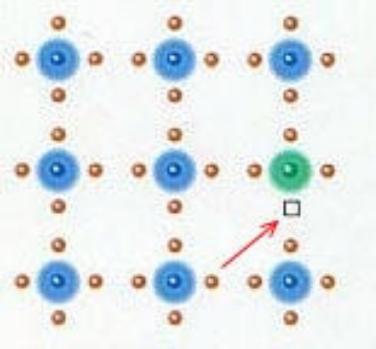
Figure 2.24



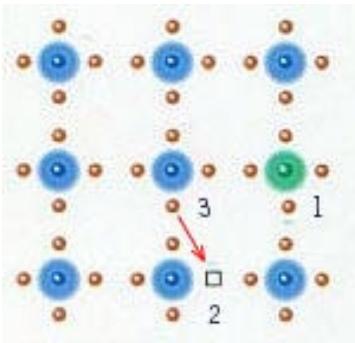
Acceptor atoms provide a deficiency of electrons to form p-type silicon.



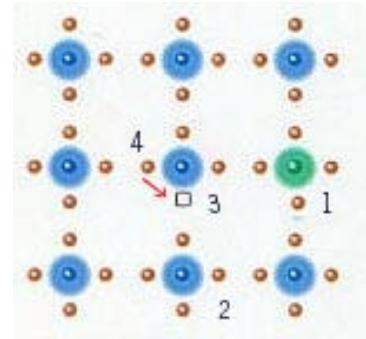
“Hole Movement in Silicon”



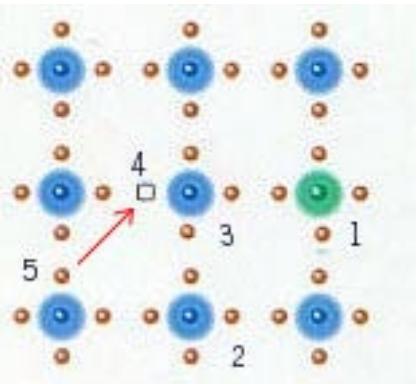
Boron is neutral, but nearby electron may jump to fill bond site.



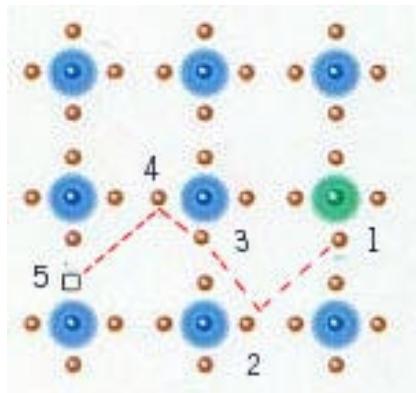
Boron is now a negative ion.



Only thermal energy to kick electrons from atom to atom.



Hole moved from 2 to 3 to 4, and will move to 5.



The empty silicon bond sites (holes) are thought of as being *positive*, since their presence makes that region positive.

Conduction in p-Type Silicon

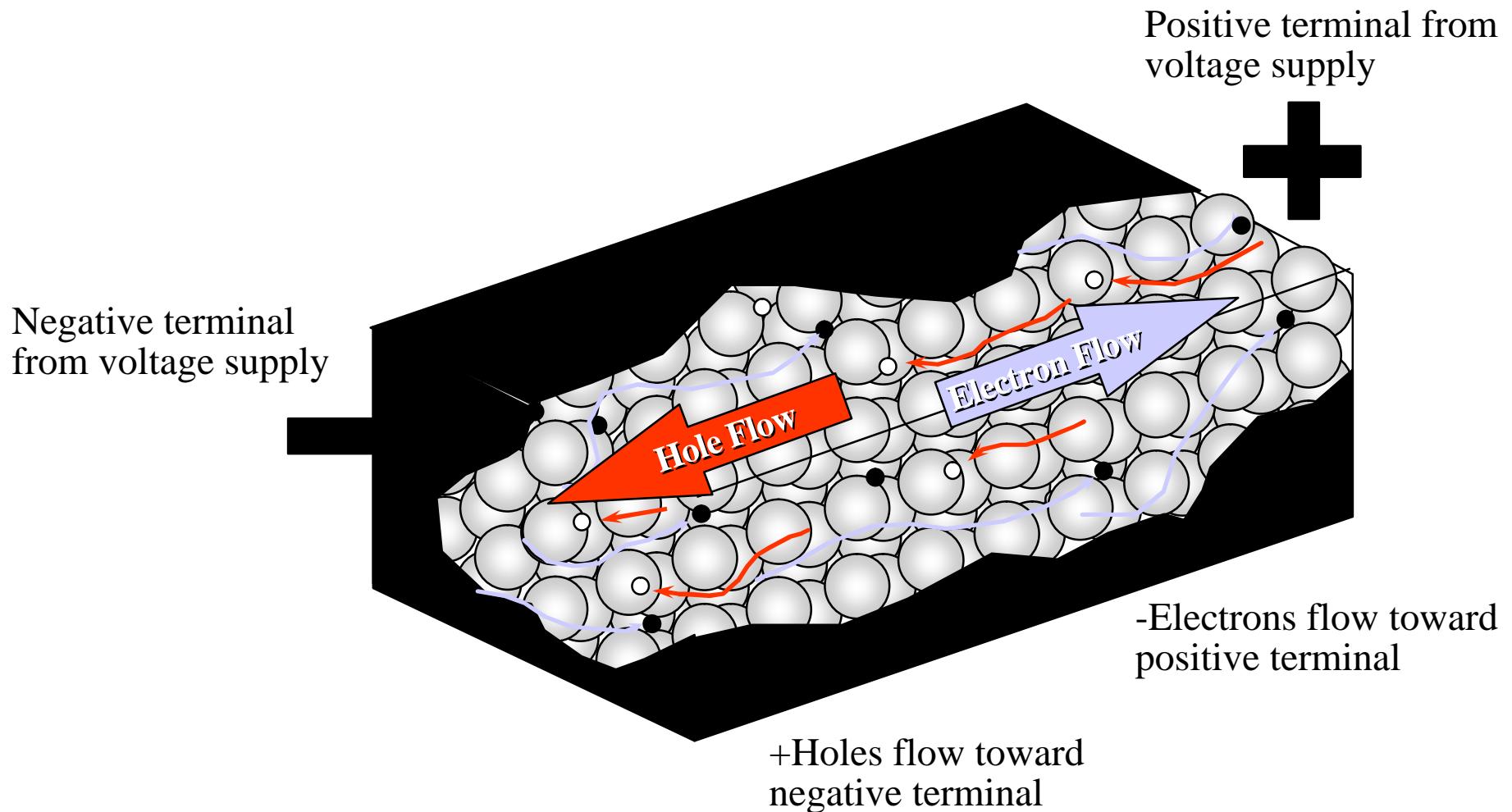


Figure 2.26

Outline

- Silicon and Silicon crystal structure
- Defect types in silicon crystals
- Silicon doping (Dopants = Defects)
- Radiation induced defects
 - Point defects and clusters
 - Particle dependence
 - Defect kinetics
 - Example of DLTS measurement
- What are defects doing to detectors?
- How to measure defects?
- Coffee



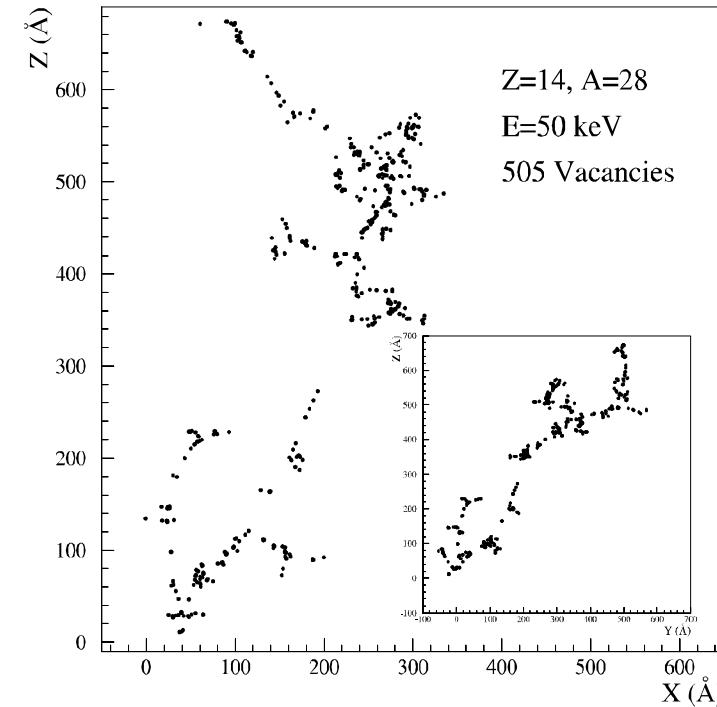
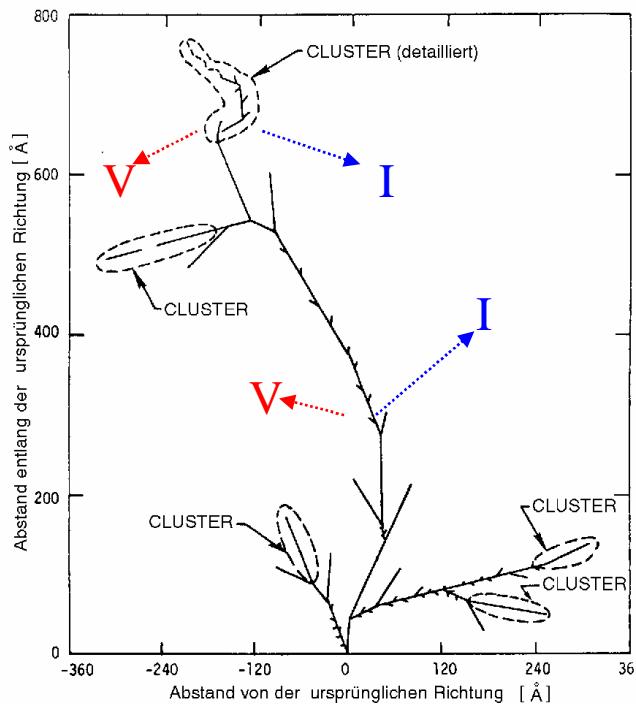
Radiation Damage – Microscopic Effects



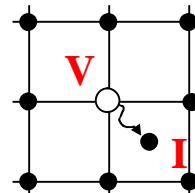
◆ Spatial distribution of vacancies created by a 50 keV Si-ion in silicon.
(typical recoil energy for 1 MeV neutrons)

M.Huhtinen 2001

van Lint 1980



particle → Si_S → $E_K > 25 \text{ eV}$



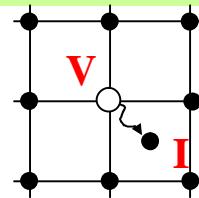
Vacancy
+
Interstitial

point defects
(V-O, C-O, ..)

$E_K > 5 \text{ keV}$ point defects and clusters of defects



particle → Si_S → $E_K > 25 \text{ eV}$



Vacancy
+
Interstitial

point defects
(V-O, C-O, ..)

$E_K > 5 \text{ keV}$ point defects and clusters of defects

- ^{60}Co -gammas

- Compton Electrons with max. $E_\gamma \approx 1 \text{ MeV}$ (no cluster production)

- Electrons

- $E_e > 255 \text{ keV}$ for displacement
- $E_e > 8 \text{ MeV}$ for cluster

- Neutrons (elastic scattering)

- $E_n > 185 \text{ eV}$ for displacement
- $E_n > 35 \text{ keV}$ for cluster

Only point defects

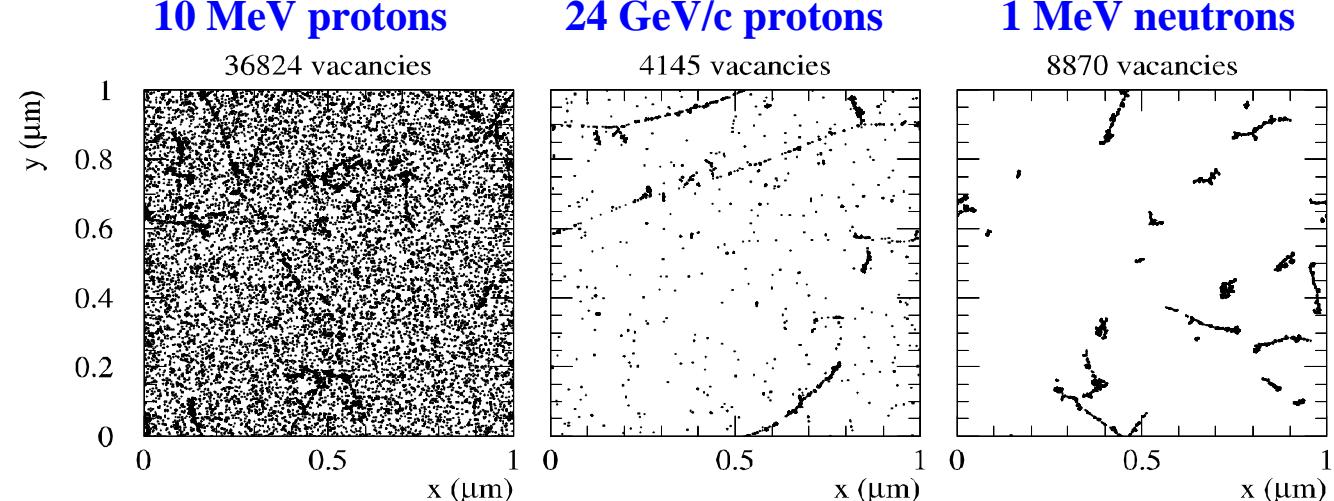
↔ point defects & clusters

↔ Mainly clusters

Simulation:

Initial distribution of vacancies in $(1\text{mm})^3$ after $10^{14} \text{ particles/cm}^2$

[Mika Huhtinen NIMA 491(2002) 194]





- Two basic defects

I - Silicon Interstitial V - Vacancy

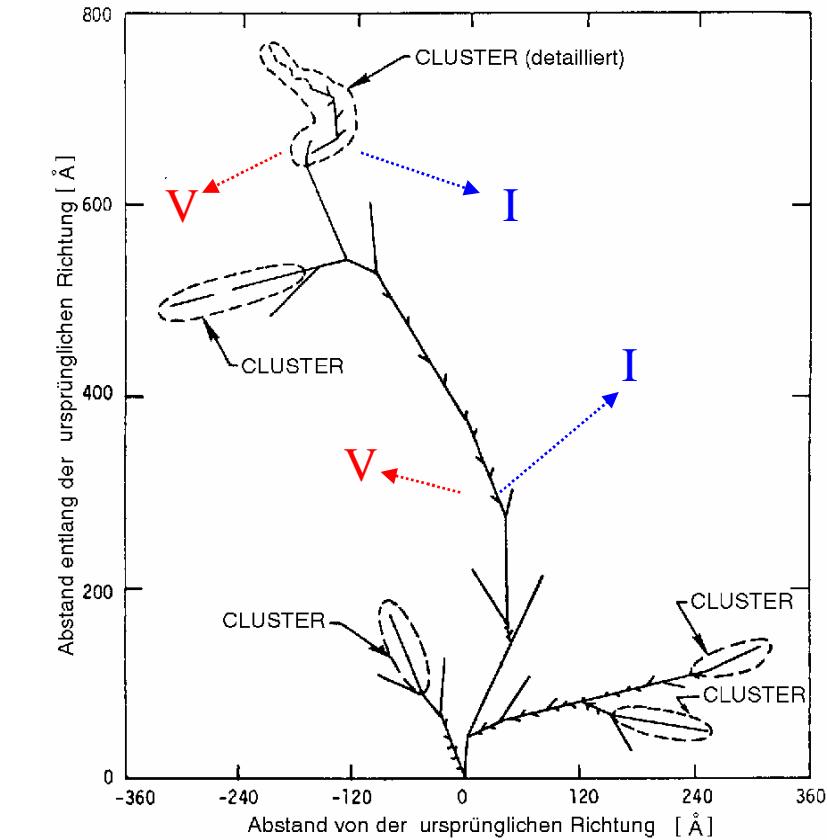
- Primary defect generation

I, I_2 higher order I (?)

P I-CLUSTER (?) ←

V, V_2 , higher order V (?)

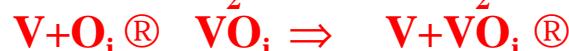
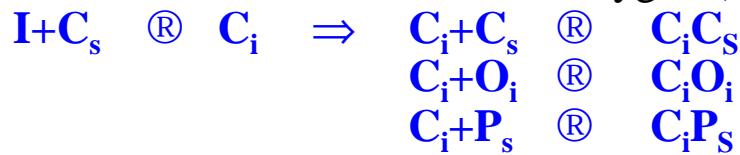
P V-CLUSTER (?) ←



- Secondary defect generation

Main impurities in silicon: Carbon (C_s)

Oxygen (O_i)



← Damage?! ("V₂O-model")



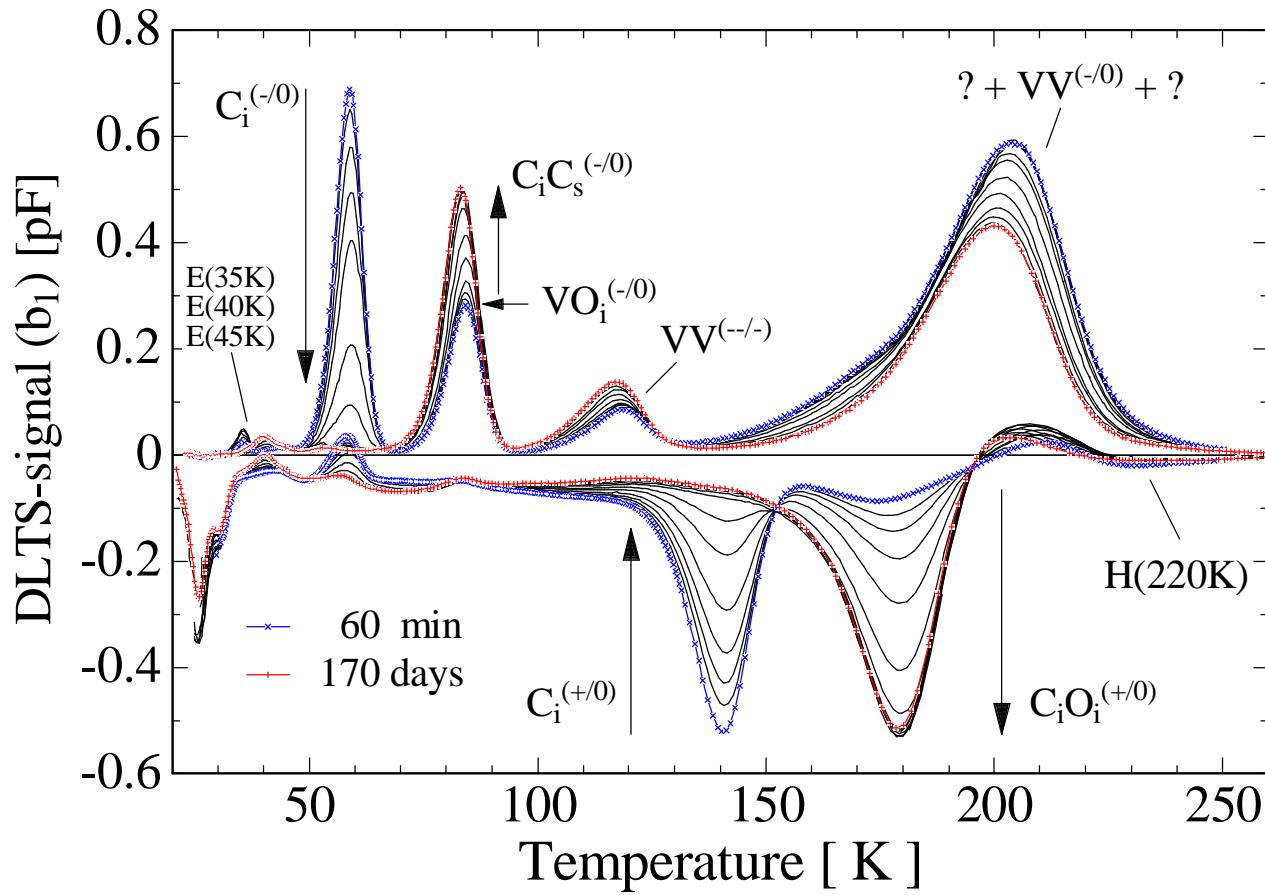
.....

Example of defect spectroscopy

- neutron irradiated -



Deep Level Transient Spectroscopy



Introduction Rates

$$N_t / F_{eq} :$$

$$C_i : 1.55 \text{ cm}^{-1}$$

$$C_i C_s : 0.40 \text{ cm}^{-1}$$

$$C_i O_i : 1.10 \text{ cm}^{-1}$$

- Introduction rates of main defects » 1 cm^{-1}
- Introduction rate of negative space charge » 0.05 cm^{-1}

$$\text{example : } F_{eq} = 1 \cdot 10^{14} \text{ cm}^{-2}$$

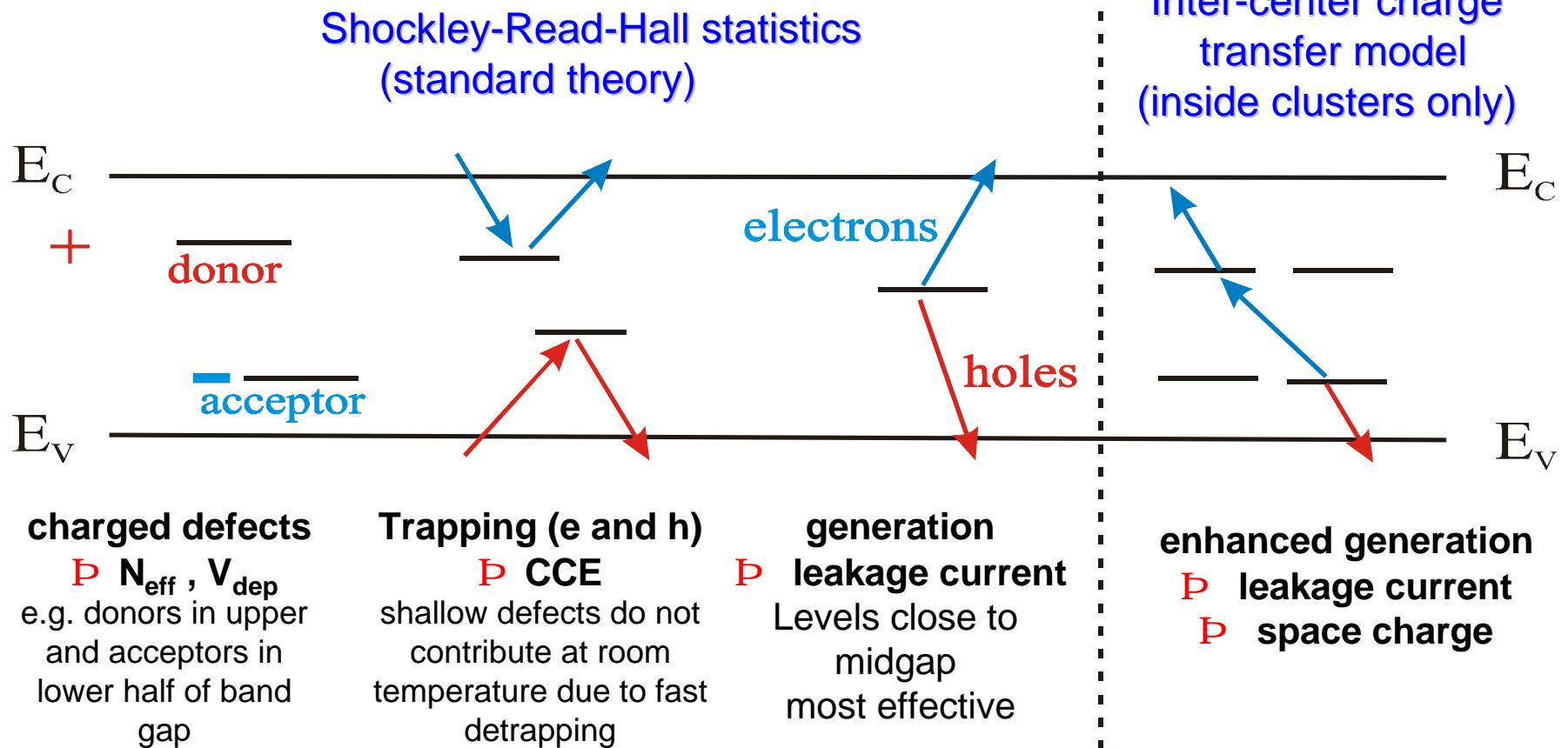
$$\text{defects } \gg 1 \cdot 10^{14} \text{ cm}^{-3}$$

$$\text{space charge } \gg 5 \cdot 10^{12} \text{ cm}^{-3}$$

Outline

- Silicon and Silicon crystal structure
- Defect types in silicon crystals
- Silicon doping (Dopants = Defects)
- Radiation induced defects
- **What are defects doing to detectors?**
- How to measure defects?
- Coffee





Impact on detector properties can be calculated if all defect parameters are known:

$s_{n,p}$: cross sections

ΔE : ionization energy

N_t : concentration

Outline

- Silicon and Silicon crystal structure
- Defect types in silicon crystals
- Silicon doping (Dopants = Defects)
- Radiation induced defects
- What are defects doing to detectors?
- How to measure defects?
 - Some measurement techniques ...
 - Deep Level Transient Spectroscopy
- Coffee





- **Structure and Chemical Configuration**
 - TEM – Transmission Electron Spectroscopy
 - EPR – Electron Paramagnetic Resonance
- **Optical properties (local vibrational modes)**
 - FTIR – Fourier Transform Infrared spectroscopy
- **Electrical Properties**
 - PL - Photoluminescence
 - TSC – Thermally Stimulated Current
 - **DLTS – Deep Level Transient Spectroscopy**
- **Binding energy and migration**
 - Annealing experiments



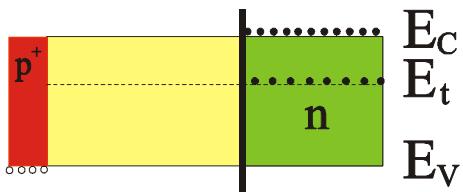
- simplified working principle -

a) Stabilize temperature

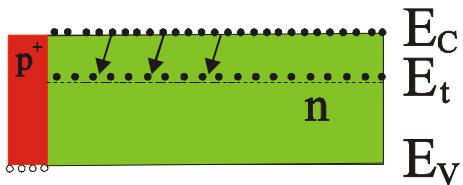
b) Variation of voltage

→ Measurement of capacitance transient

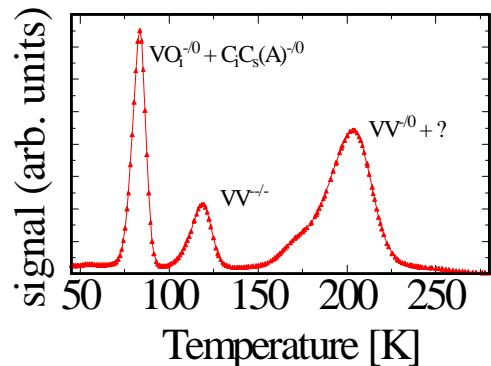
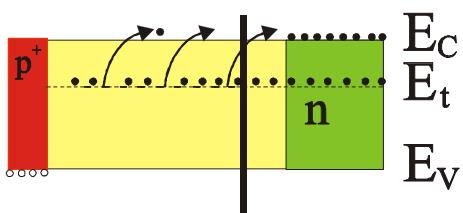
1) reverse bias



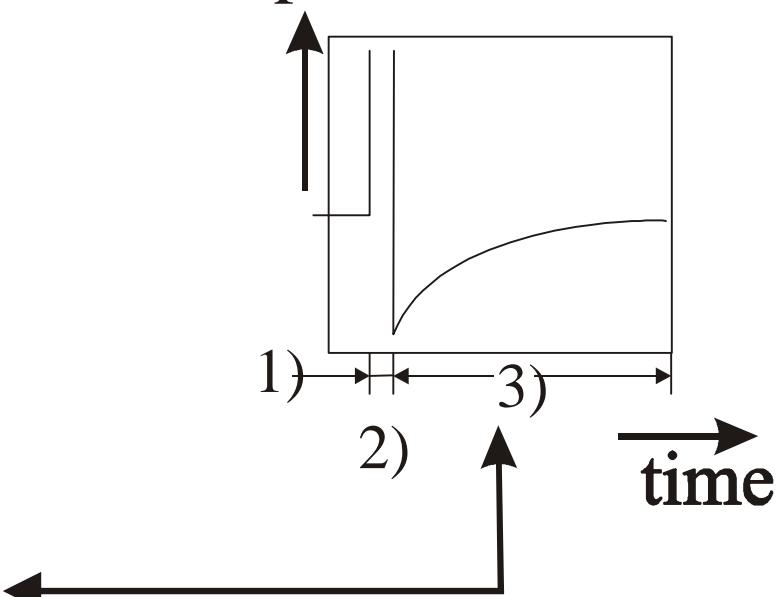
2) zero bias



3) reverse bias



Capacitance

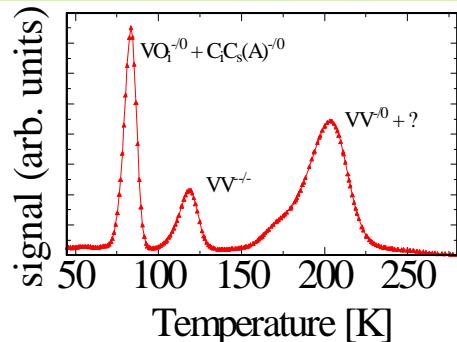
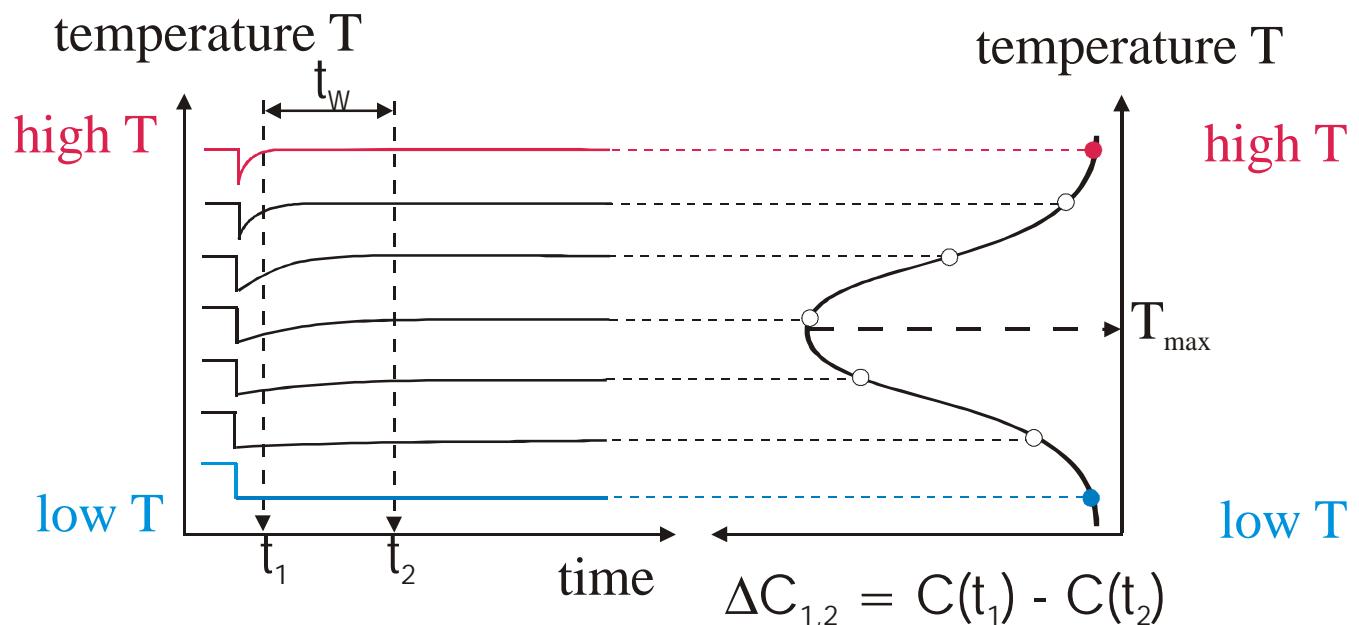


$$C \propto \frac{1}{W} \propto \sqrt{N_{eff}}$$



- simplified working principle -

c) Measure capacitance transients at many temperatures
→ DLTS - spectrum



c) Analyze the DLTS-spectra (“Arrhenius Plots”)

▷ extract defect parameters :

E_t position in bandgap

S_n, S_p cross sections for electrons and holes

N_t defect concentration



Coffee !!!!!



Coffee !!!!!

